## **REMARKS/ARGUMENTS**

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

Claims 1, 3, 11, 18, 20, and 22 are presently active. Claims 2, 4-10, 12-17, 19, 21, and 23-39 are withdrawn. Claims 1 and 18 have been presently amended.

In the outstanding Office Action, Claims 1, 3, 11, 18, 20, and 22 were rejected under 35 U.S.C. § 102(b) as being anticipated by U.S. Pat. No. 6,367,412 to Ramaswamy et al.

The present amendments make clear that the defined passive component of the processing element is disposed proximate or opposing a substrate position in the semiconductor manufacturing system, as illustrated in Applicants' Figures 1-5. In Ramaswamy et al, the porous ceramic liners associated in the Office Action with the passive component of the present invention are disposed in plasma tube 30 removed from the substrate 14, as seen in Figures 2 and 3 of Ramaswamy et al.

Hence, it is respectfully submitted that independent Claims 1 and 18 (and the claims dependent therefrom) patentably define over the cited art of record. Accordingly, it is requested that Claims 2, 4-10, 12-17, 19, 21, and 23-26 (which depend from either Claim 1 or Claim 18) be rejoined and allowed.

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Consequently, in view of the present amendment and in light of the above discussions, the outstanding grounds for rejection are believed to have been overcome. The application as amended herewith is believed to be in condition for formal allowance. An early and favorable action to that effect is respectfully requested.

Respectfully submitted,

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